



## Future Normal in Semiconductor

2025-02-14(금), 15:10-17:10

좌장: 추후업데이트 예정

### B. Patterning (Lithography & Etch Technology) 분과

#### [FL3-B] Etch

<p><b>초청</b> FL3-B-1 15:10-15:40</p>	<p><b>Semiconductor Equipment Technology: What's Next?</b> Dougyong Sung Mechatronics Research, Samsung Electronics Co., Ltd.</p>
<p>FL3-B-2 15:40-15:55</p>	<p><b>Low-temperature SiO<sub>2</sub> contact hole etching using C<sub>4</sub>F<sub>8</sub> plasmas</b> 유상현<sup>1,2</sup>, 김창구<sup>1,2</sup> <sup>1</sup>Department of Chemical Engineering, Ajou University, <sup>2</sup>Department of Energy Systems Research, Ajou University</p>
<p>FL3-B-3 15:55-16:10</p>	<p><b>High-throughput Isotropic Atomic Layer Etching of Hafnia Films Using F Radicals and Al Precursors</b> Gyejun Cho, Jehwan Hong, Hye-Lee Kim, and Won-Jun Lee Department of Nanotechnology and Advanced Materials Eng., Sejong University</p>
<p><b>초청</b> FL3-B-4 16:10-16:40</p>	<p><b>Technical Challenge and Development of HARC Etching</b> Sang Wook Park, Jae Won Lee, Sang Heon Song, Kyung Tae Kim, Ki Jun Yun, Hoo Woong Lee, Woo June Kwon, Chung Won Seo, and Hyun Min Lee SK hynix</p>
<p>FL3-B-5 16:40-16:55</p>	<p><b>Investigation on the Effect of Tailored Waveform Bias on the Formation of SiO<sub>2</sub>/Si Trench Etch Profile in SF<sub>6</sub>/O<sub>2</sub>/Ar Plasma</b> Taejun Park<sup>1</sup>, Jihoon Park<sup>1</sup>, Ingyu Lee<sup>1</sup>, Namkyun Kim<sup>2</sup>, and Gon-Ho Kim<sup>1</sup> <sup>1</sup>Seoul National University, <sup>2</sup>Samsung Electronics</p>
<p>FL3-B-6 16:55-17:10</p>	<p><b>Ultrathin Ni catalyst for CMOS-compatible Metal-assisted Chemical Etching of Si</b> Kyunghwan Kim<sup>1,2</sup>, Haekyun Bong<sup>1,3</sup>, and Jungwoo Oh<sup>1,3</sup> <sup>1</sup> School of Integrated Technology, Yonsei University, <sup>2</sup>Center for Quantum Technology, KIST, <sup>3</sup>BK21 Graduate Program in Intelligent Semiconductor Technology, Yonsei University</p>



# 제 32회 한국반도체학술대회

The 32nd Korean Conference on Semiconductors

2025년 2월 12일(수)-14일(금) | 강원도 하이원리조트

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<b>초청</b> FM3-T-1 15:10-15:40	<b>Mobilint AI Chips: Powering On-device and On-premises AI</b> Dongjoo Shin Mobilint, Inc., Korea
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